

**IN THE SPECIFICATION:**

**Please amend page 2, the fourth paragraph as amended below:**

United States patents 3,353,924, 3,855,068, 3,824,080 and 5,567,396 ~~US A 3 353 924, US A 3 855 068, US A 3 824 080 and US A 5 567 396~~ describe, for example, systems for staged injection of gas between two beds in which injection of the secondary gas, the secondary gas/primary flow mixture and distribution of the mixture are decoupled and are carried out successively. In contrast, in the devices described in the present application, the functions of injection, mixing and distribution of the two incident fluids are carried out simultaneously in the same system.

**Please amend the first paragraph at page 3 as indicated below:**

U.S. Patent No. 4,235,847 ~~US A 4 235 847~~ describes a system in which two secondary injection stages are possible (one of gas and one of liquid). At the bed outlet, the gas/liquid flow is separated via a system of baffles. The liquid is collected at a plate with a diameter that is less than the diameter of the reactor and the gas is injected below this plate into the volume of liquid collected. The gas/liquid mixture (in the form of a mist) is then recovered from the top of tubes and injected into the bed through those tubes. That system integrates the function of gas/liquid mixing and distribution of the mixture at a single plate, but has the major drawback of limiting distribution to a diameter of less than the diameter of the plate because of the system of baffles. Further, the mixture is recovered from a single level in the conduits, that plate causes flexibility problems as regards the liquid flow. Finally, heat exchange occurs firstly from a gas to a gas and then from the resulting gas to a liquid. For the same interfacial area developed, there is thus a loss in gas/liquid heat transfer efficiency with respect to the case where the secondary gas (cold)

is brought into direct contact with the liquid.

**Please amend the last paragraph on page 6 bridging page 7 as indicated below:**

The liquid feed (1) is injected into the head of the reactor. The gas feed (2) is injected at two levels upstream of reactor (60): the head of the reactor via line (7) and to an intermediate level of the reactor via line (9), via a distribution means (200 or 220) located between two successive beds. To optimise material exchange between the gas feed and the liquid feed upstream of the reactor, a fraction of the gas feed injected overhead is injected via line (8) and a buffer drum (50). Distribution of the gas flow injected between lines (7), (8), ~~and (9) and (12)~~ is controlled using regulating valves (10) and (11). The gas flow injected into reactor (60) via line (7) is normally in the range 0 mole % to 70 mole % of the total molar flow of the gas injected into reactor (60); the gas flow injected into reactor (60) via line (8) is normally in the range 0 mole % to 70 mole % of the total molar flow rate of the gas injected into reactor (60), and the gas flow rate injected via line (9) is in the range 30 mole % to 50 mole % of the total molar flow of the gas injected into reactor (60). At the reactor inlet, the liquid feed can be directly injected into the distribution means (100) located at the head of the reactor via line (3), or it can be injected via line (4) and buffer drum (50) prior to rejoining the distribution means (100) via line (13). Liquid flow via lines (3) and (4) is controlled by regulating valves (5). The fraction of the liquid feed flow injected into the reactor via line (4) is in the range 1% to 99% by weight of the total liquid flow injected into the reactor and the fraction of the flow of liquid feed injected into the reactor via line (3) is in the range 99% to 1% by weight of the total liquid flow rate injected into the reactor. After the reaction, the product is recovered via line (15).